

VACUUM DEPOSITION TECHNOLOGIES FOR FILMS AND COATINGS

17-20 February 2014 Salón de Actos CicCartuja

Time Monday 17

15:00-19:00 Kinetic theory of gas
Plasma discharge
(30 minutes break)
Magnetron sputtering
(Stephane Lucas – University of Namur)

Time Tuesday 18

15:00-17:00 High Power Impulse Magnetron Sputtering for thin film deposition: why and how
(Stephanos Konstantinidis – University of Mons)
17:00-17:30 Break
17:30-19:00 Fundamentals and Process-Control in Physical Vapor Deposition of Thin Films
(Alberto Palmero – Instituto Ciencia de Materiales de Sevilla)

Time Wednesday 19

15:00-16:30 Functional coatings prepared by magnetron sputtering for innovative applications
(Asuncion Fernandez - Instituto Ciencia de Materiales de Sevilla)
16:30-17:00 Break
17:00-19:00 Vacuum Cathodic Arc Deposition: Fundamentals and Applications
(Arturo Lousa - Universitat de Barcelona)

Time Thursday 20

15:00-17:00 Recent advances in the synthesis of multifunctional nanostructured thin films by PECVD
(Angel Barranco - Instituto Ciencia de Materiales de Sevilla)
17:00-17:30 Break
17:30-18:30 Laser assisted surface functionalization
(German de la Fuente - Instituto de Ciencia de Materiales de Aragón)

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